

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	25	("cvp" or cvd "vapor deposition") near5 (chamber or vessel) same "self cleaning"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 09:43
S2	166	("cvp" or cvd "vapor deposition") and ((chamber or vessel) same "self cleaning")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/16 09:51
S3	166	("cvp" or cvd "vapor deposition") and ((chamber or vessel) same "self cleaning")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 09:43
S4	174	("cvp" or cvd "vapor deposition") and ((chamber or vessel or processor) same "self cleaning")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 09:44
S5	20887	("cvp" or cvd "vapor deposition") and (reactor or (chamber or vessel or processor) same "self cleaning")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 09:44
S6	193	("cvp" or cvd "vapor deposition") and ((reactor or chamber or vessel or processor) same "self cleaning")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 09:50
S7	497661	\$6fluori\$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 09:49
S8	100	("cvp" or cvd "vapor deposition") and ((reactor or chamber or vessel or processor) same "self cleaning") and \$6fluori\$6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/15 09:51

S9	42	("cvp" or cvd "vapor deposition") and ((reactor or chamber or vessel or processor) same "self cleaning") and (\$6fluori\$6 and (microwave or magnetron)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:14
S10	100	("cvp" or cvd "vapor deposition") and ((reactor or chamber or vessel or processor) same ("self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (\$6fluori\$6 near10 (gas or vapor or atmosphere or fog or aerosol or mist or gaseous)) and (magnetron or microwave)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 09:01
S11	2	("6294085").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 10:17
S12	0	("55378375").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 10:17
S13	2	("5378375").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 10:20
S14	2	("5122263").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 10:24
S15	2	("5341826").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 10:26
S16	2	("5557845").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 10:27

S17	2	("5570845").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 10:27
S18	100	("cvp" or cvd "vapor deposition") and ((reactor or chamber or vessel or processor) same ("self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (\$6fluori\$6 near10 (gas or vapor or atmosphere or fog or aerosol or mist or gaseous)) and (magnetron or microwave)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 08:37
S19	6704	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near25 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 08:42
S20	3239	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near25 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (deposit\$6 near15 (temperature or degree or "F" or "C")) (clean\$6 near15 (temperature or degree or "F" or "C")) and (\$6fluori\$6 near10 (magnetron or microwave))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 08:46
S21	60	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near10 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C")) and (\$6fluori\$6 near10 (magnetron or microwave))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 08:47

S22	60	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near25 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C")) and (\$6fluori\$6 near10 (magnetron or microwave))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 08:48
S23	229	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near25 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C")) and (\$6fluori\$6 same (magnetron or microwave))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:15
S24	100	("cvp" or cvd "vapor deposition") and ((reactor or chamber or vessel or processor) same ("self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (\$6fluori\$6 near10 (gas or vapor or atmosphere or fog or aerosol or mist or gaseous)) and (magnetron or microwave)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 08:49
S25	210	S23 not S24	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:31
S26	2	("20030066541").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/18 09:01
S27	73	S25 not "applied materials"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 09:09

S28	1	"6767834" and (deposit\$6 near15 (temperature or degree or "F" or "C"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 09:55
S29	2	"6673262" and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:36
S30	2	"6673262" and (deposit\$6 near15 (temperature or degree or "F" or "C"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:03
S31	1	"6443165" and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:21
S32	0	"6443165" and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C")) and tungsten	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:21
S33	229	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near25 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C")) and (\$6fluori\$6 same (magnetron or microwave))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:31
S34	100	("cvp" or cvd "vapor deposition") and ((reactor or chamber or vessel or processor) same ("self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and (\$6fluori\$6 near10 (gas or vapor or atmosphere or fog or aerosol or mist or gaseous)) and (magnetron or microwave)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:31

S35	210	S33 not S34	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:31
S36	73	S35 not "applied materials"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:31
S37	137	S35 not S36	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 10:32
S38	18	"5788799" and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:02
S39	15	" 5812403" and (deposit\$6 near15 (temperature or degree or "F" or "C")) and (clean\$6 near15 (temperature or degree or "F" or "C"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:03
S40	33	" 5812403" and (clean\$6 near15 (temperature or degree or "F" or "C"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:06
S41	63	" 5812403"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:06
S42	437	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near25 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and ((shower or nozzle or distrib\$6) near20 (cooled or cool or water) and (heat or heated or heater or hot))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:17

S43	279	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near25 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and ((shower or nozzle or distribut\$6) near20 (cooled or cool or water) and (heat or heated or heater or hot))	USPAT	OR	ON	2005/06/18 11:18
S44	258	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near10 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and ((shower or nozzle or distribut\$6) near20 (cooled or cool or water) and (heat or heated or heater or hot))	USPAT	OR	ON	2005/06/18 11:20
S45	3504	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near25 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6)))	USPAT	OR	ON	2005/06/18 11:18
S46	53729	((shower or nozzle or distribut\$6) near20 (cooled or cool or water) and (heat or heated or heater or hot))	USPAT	OR	ON	2005/06/18 11:19
S47	279	S45 and S46	USPAT	OR	ON	2005/06/18 11:21
S48	163	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near10 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and ((shower or nozzle or distribut\$6) near20 ((cooled or cool or water) and (heat or heated or heater or hot)))	USPAT	OR	ON	2005/06/18 11:26
S49	163	S45 and S48	USPAT	OR	ON	2005/06/18 11:22
S50	59	("cvp" or cvd or "vapor deposition") and ((reactor or chamber or vessel or processor) near10 (cleaning or "self cleaning" or ("insitu near5 clean\$6") or ("in-situ" near5 clean\$6))) and ((shower or nozzle) near20 ((cooled or cool or water) and (heat or heated or heater or hot)))	USPAT	OR	ON	2005/06/18 11:22
S51	59	S45 and S50	USPAT	OR	ON	2005/06/18 11:22

S52	28	"5647945"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:33
S53	1	"20020052124" and tungsten	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:41
S54	0	"6673262" and (shower or nozzle or distributor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:43
S55	8	"10239338" or """10239339""""	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:44
S56	8	"09349536" or "10239338" or "10239339"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:48
S57	3	"6673262"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 12:30
S58	1915	mori and cvd	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:50
S59	153	mori and cvd and microwave	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:52

S60	0	"isamu mori" and cvd and microwave	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:52
S61	2	(isamu near5 mori) and cvd and microwave	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 11:53
S62	2	"6673262" and (microwave or magnetron)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 12:46
S63	0	"09349536"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/18 12:46